

Fig. 1

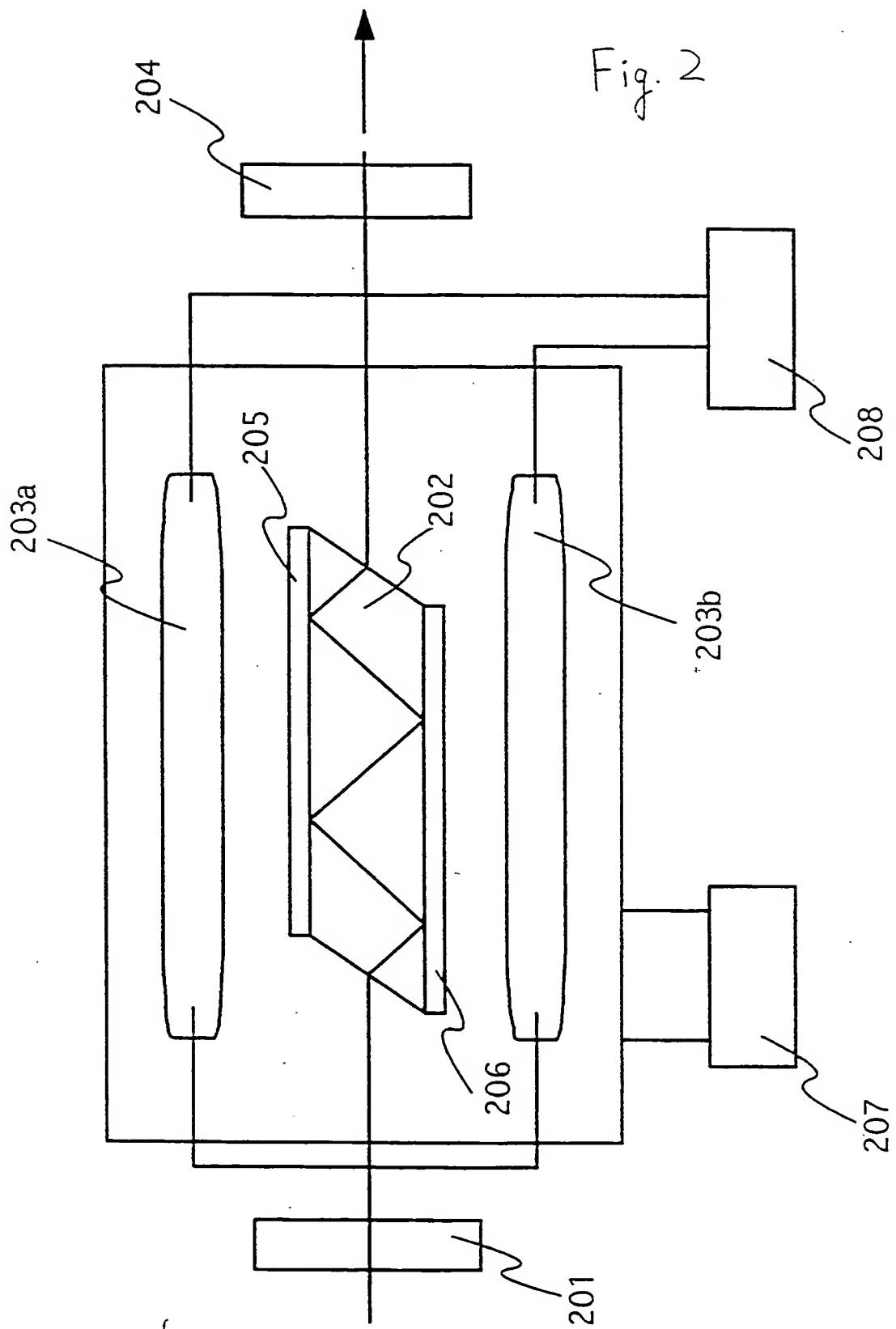
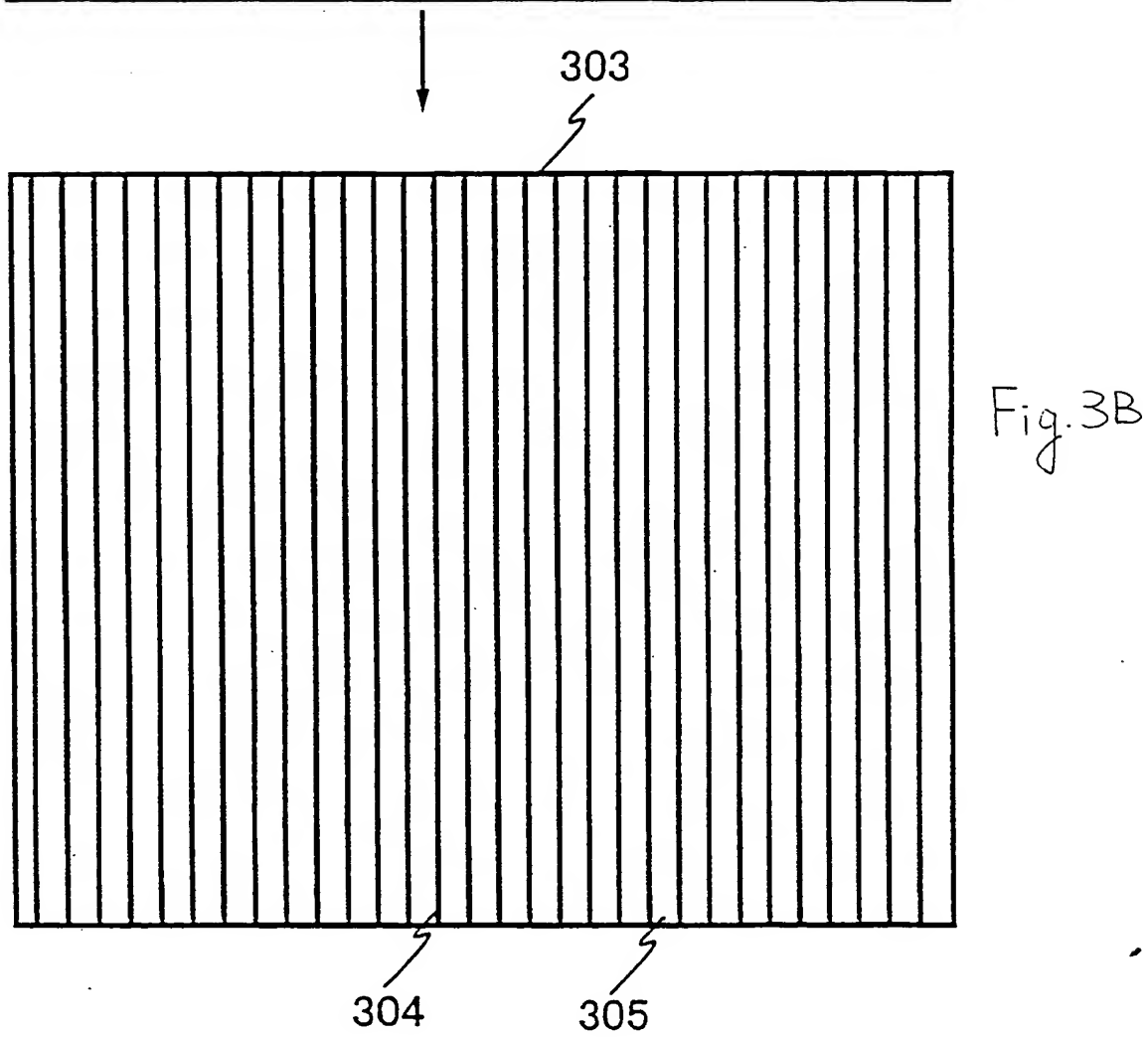
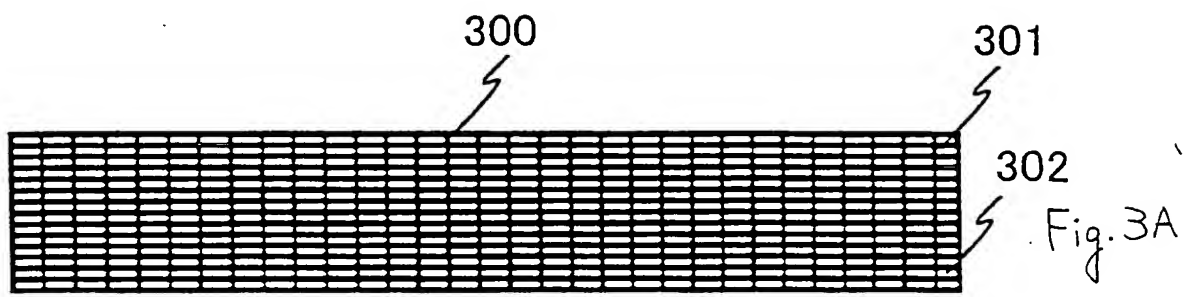
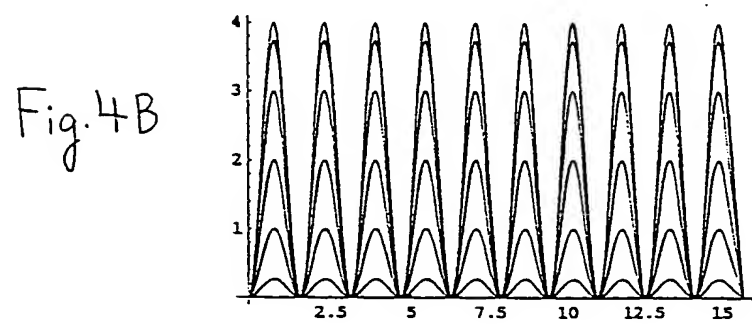
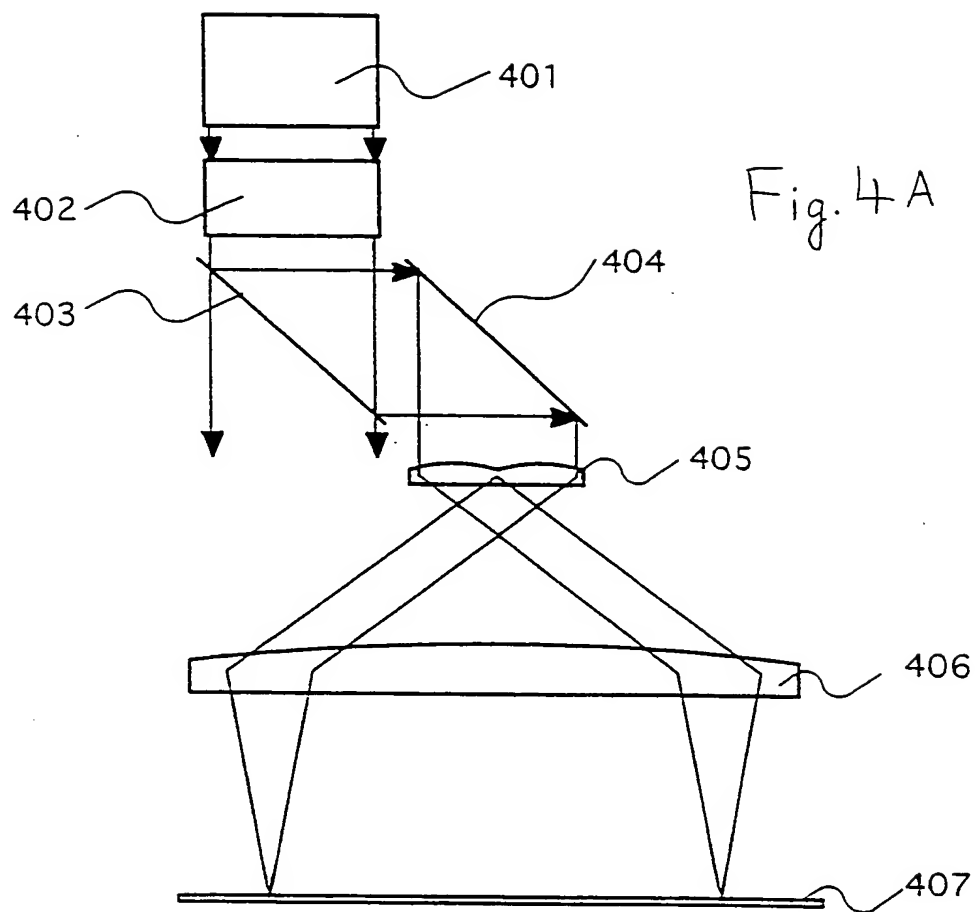


Fig. 2





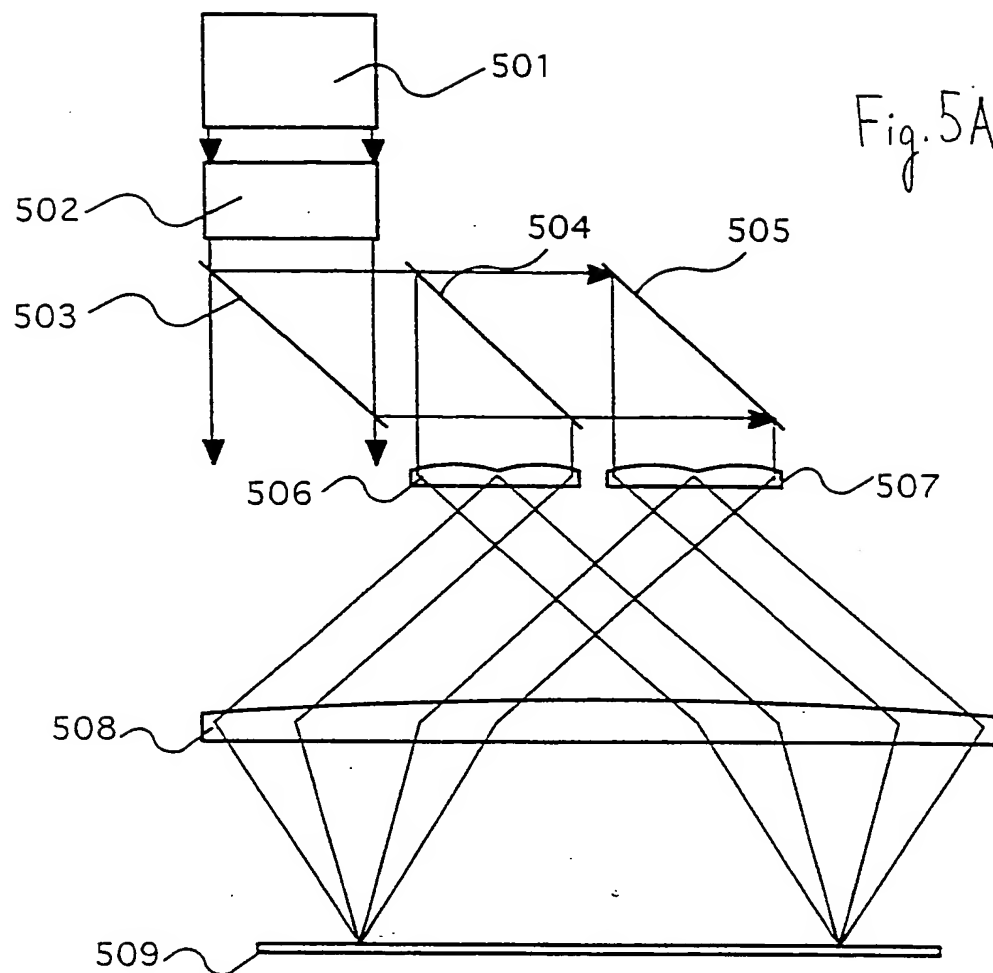
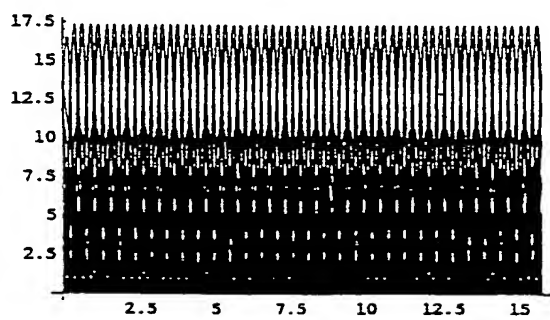


Fig. 5B



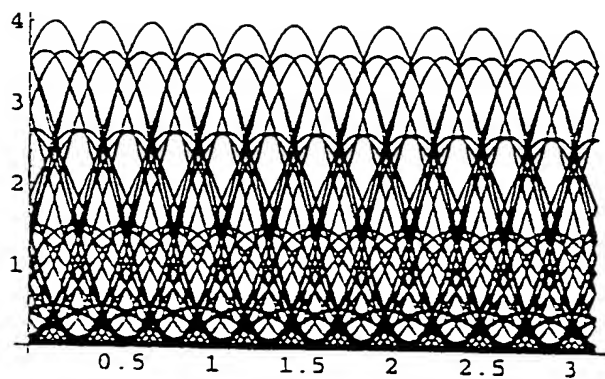


Fig. 6

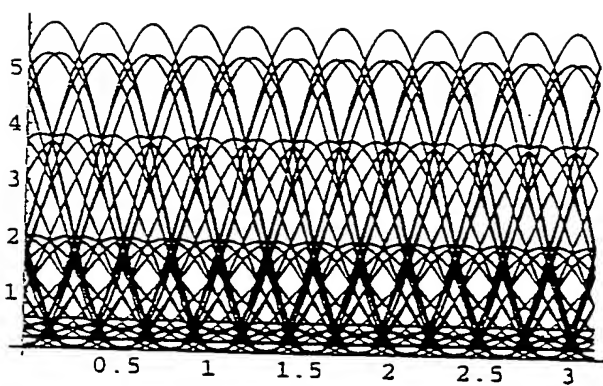


Fig. 7

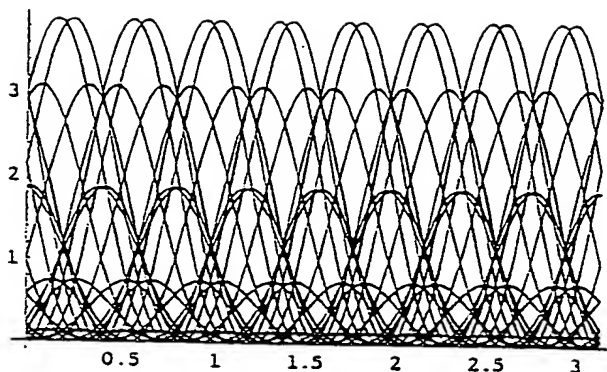


Fig. 8

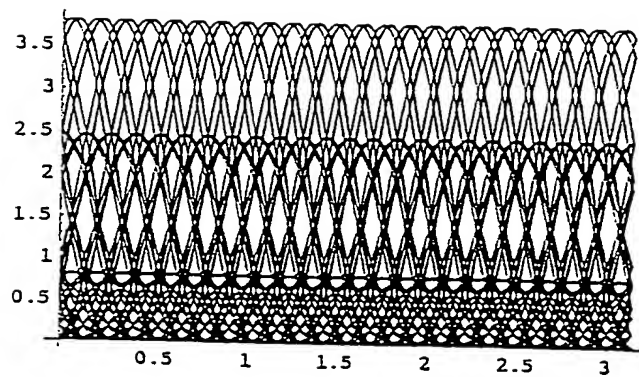


Fig. 9

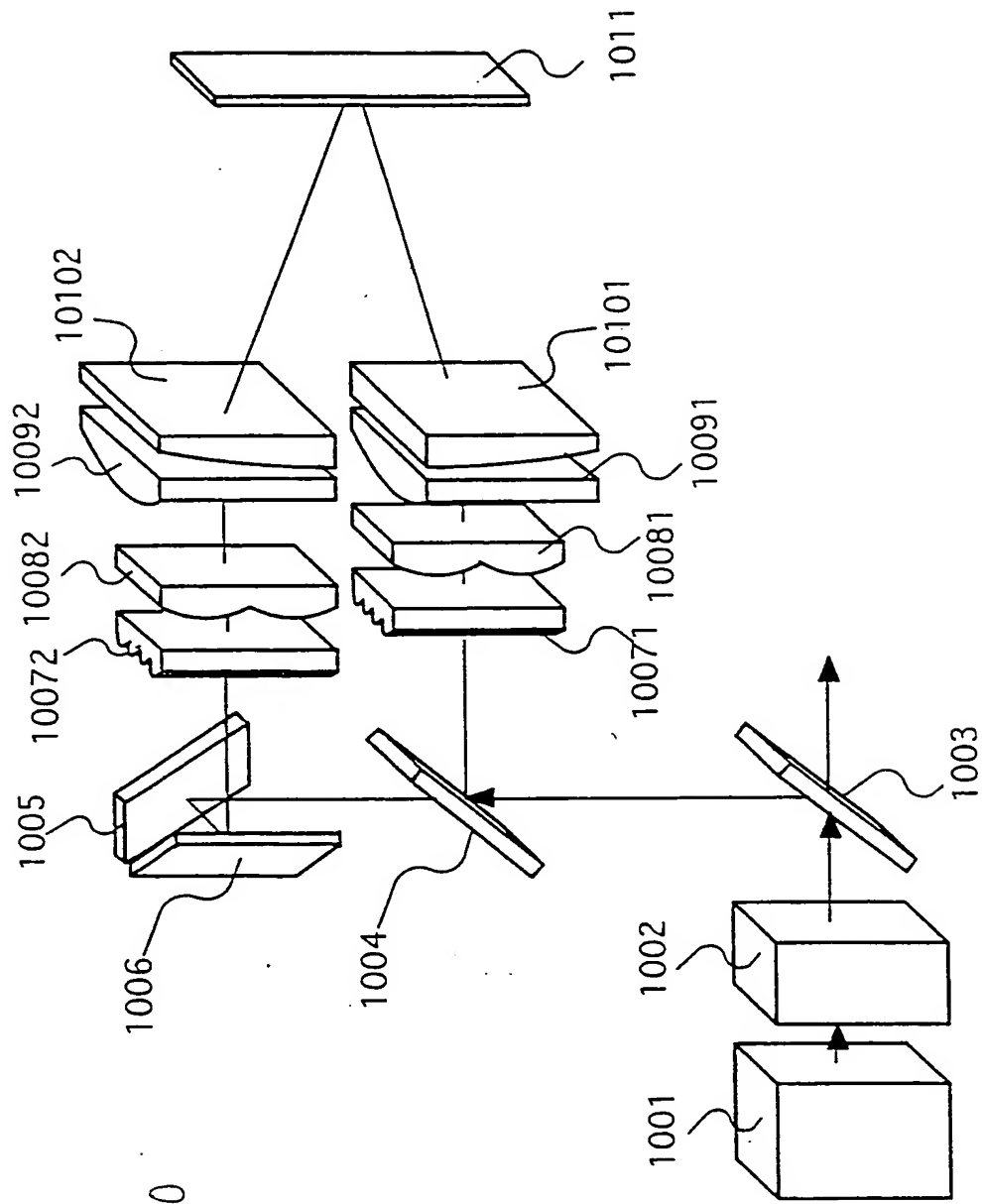


Fig. 10

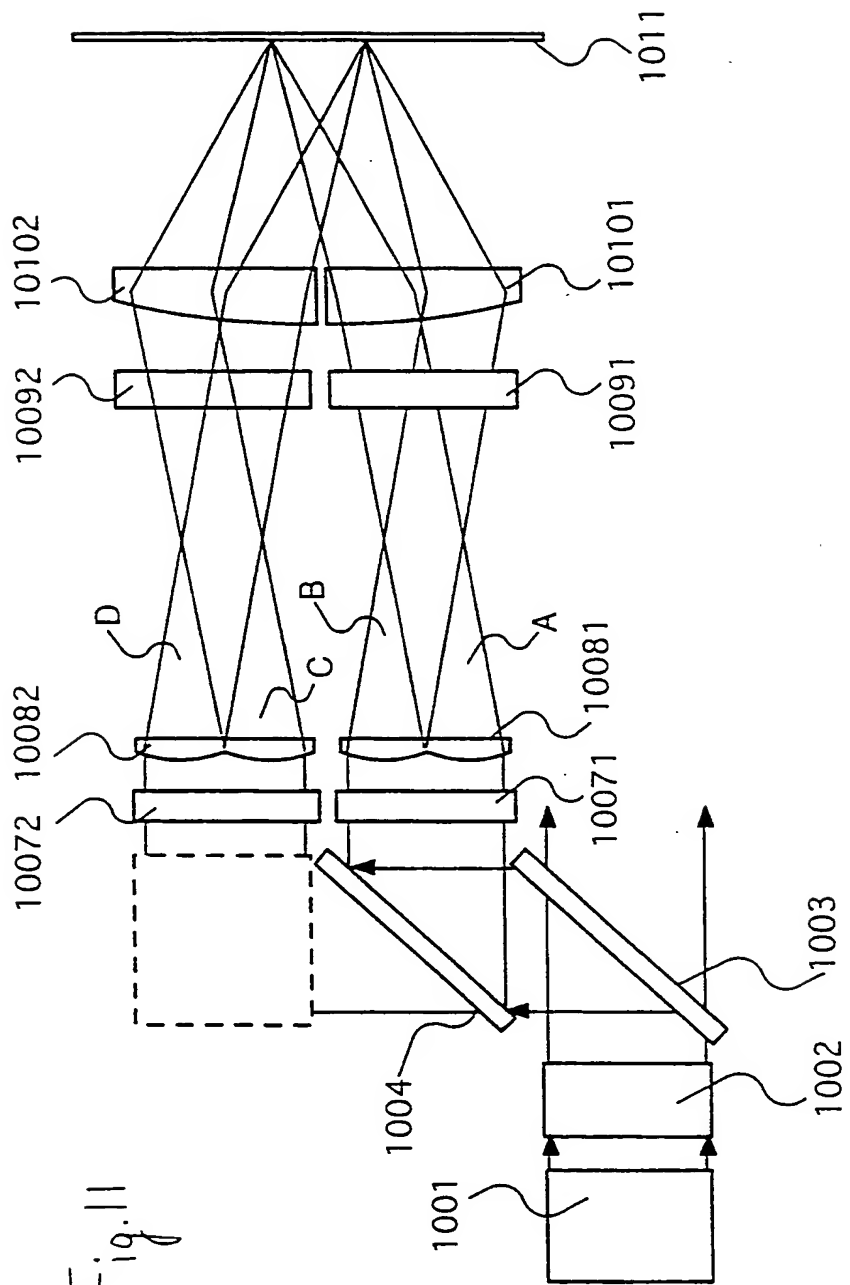


Fig. 12A

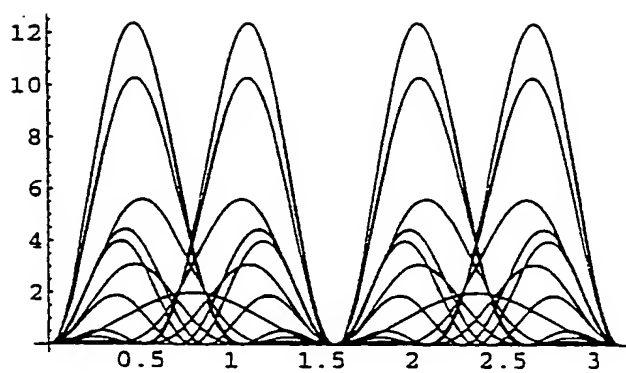
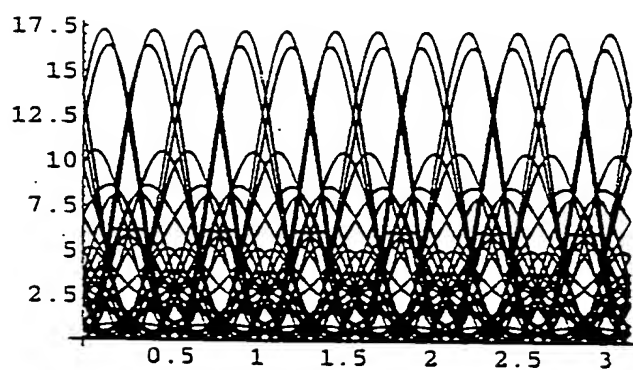


Fig. 12B



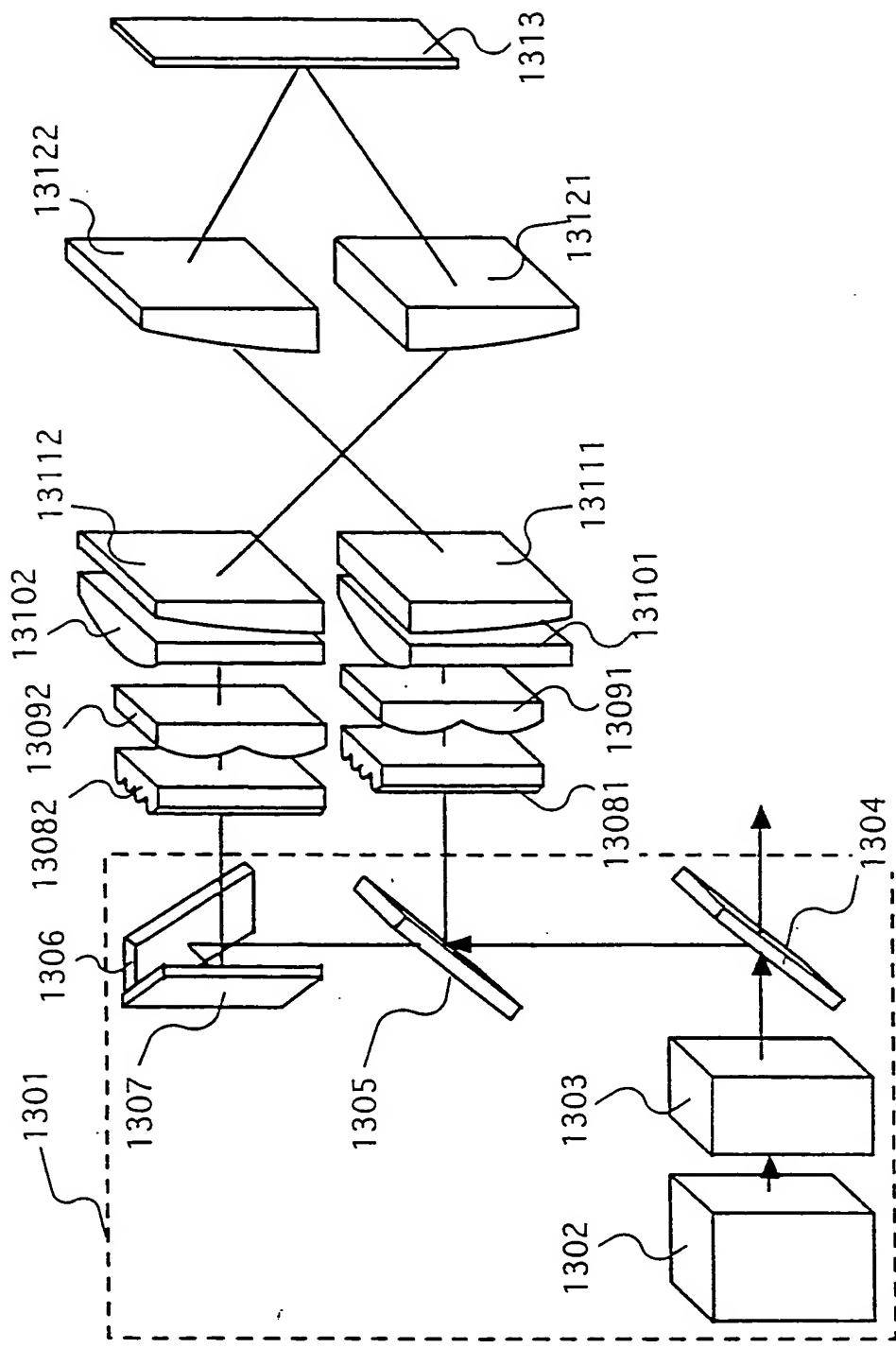
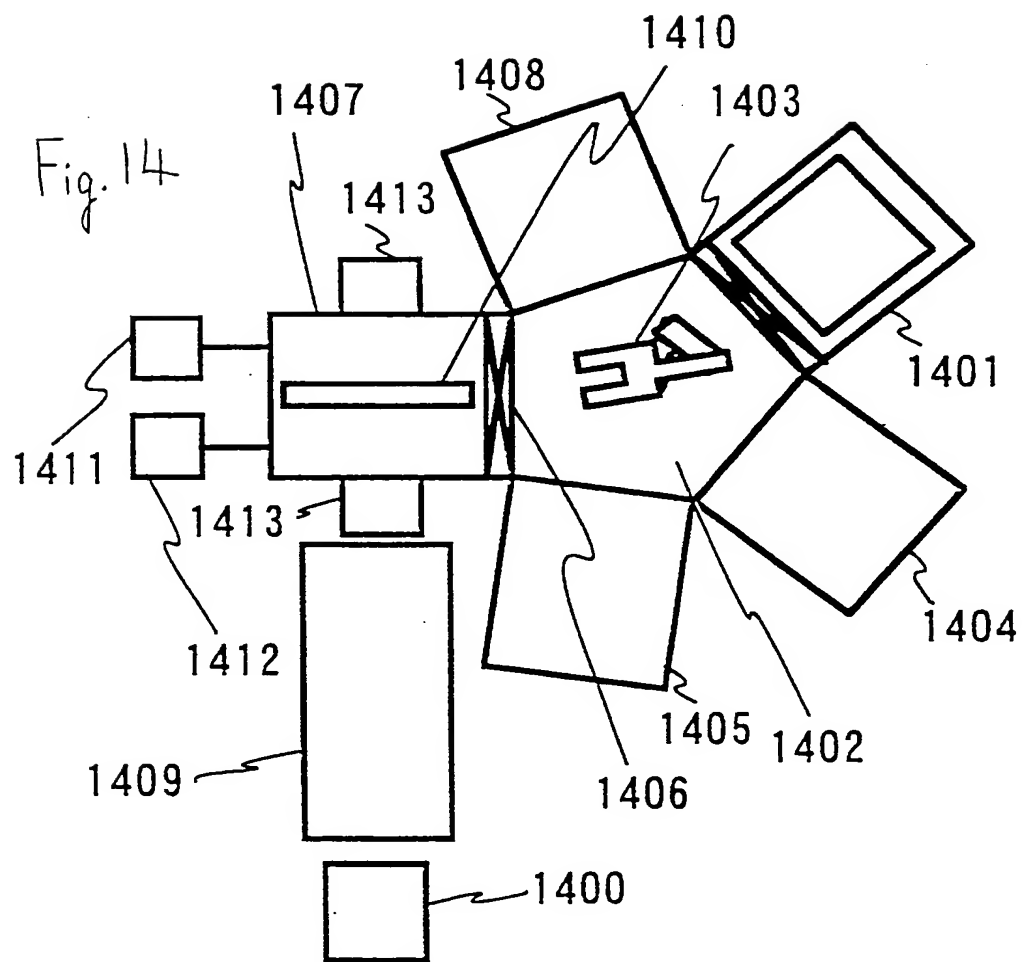
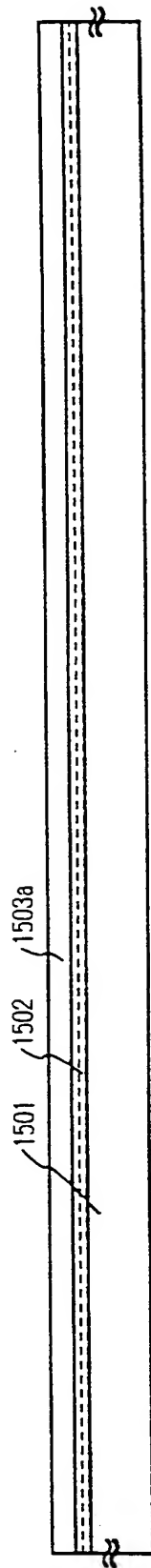


Fig. 13



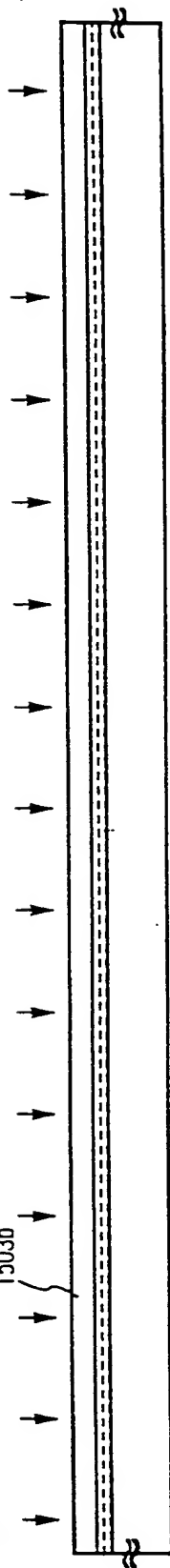
STEP OF FORMING AMORPHOUS SEMICONDUCTOR FILM

Fig.15A



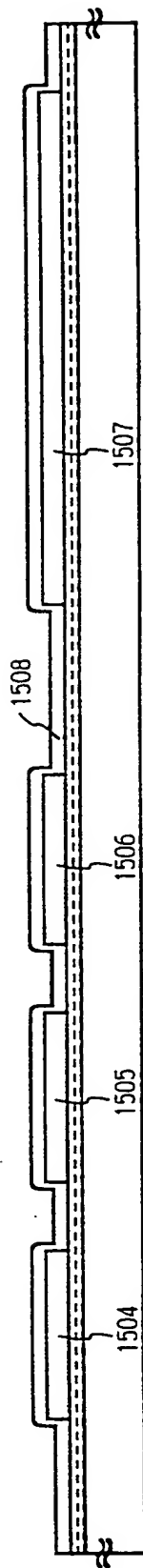
CRYSTALLIZATION STEP 1503b

Fig.15B



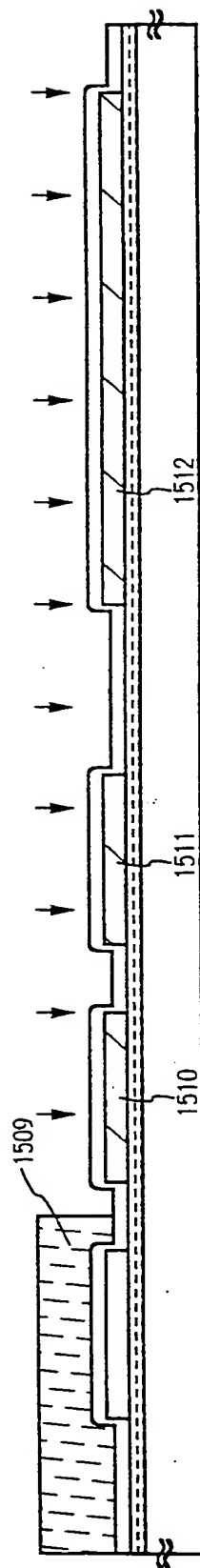
STEP OF FORMING MASK LAYER

Fig.15c



CHANNEL DOPE STEP

Fig.15D



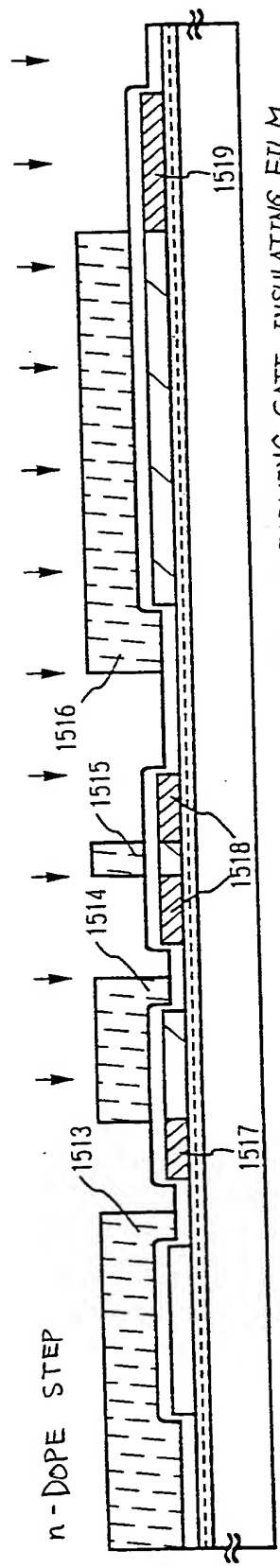


Fig. 16A

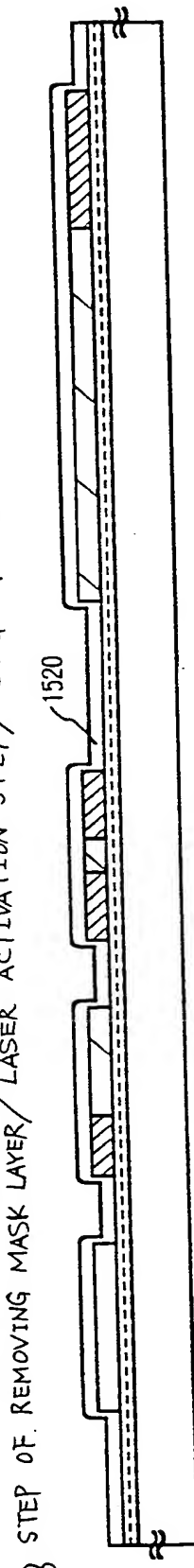


Fig. 16B

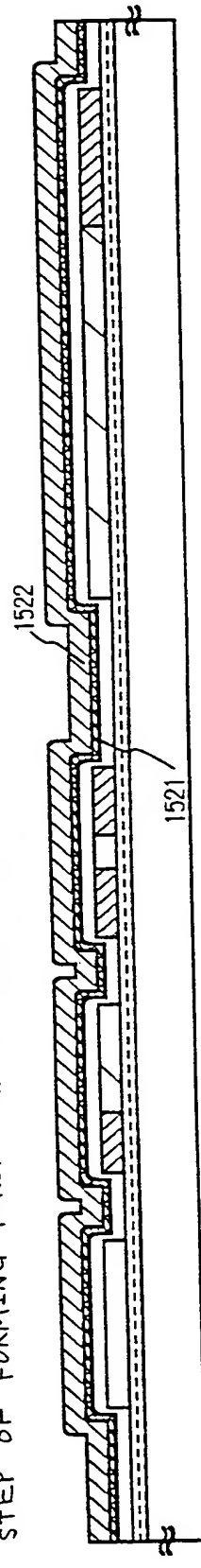


Fig. 16C

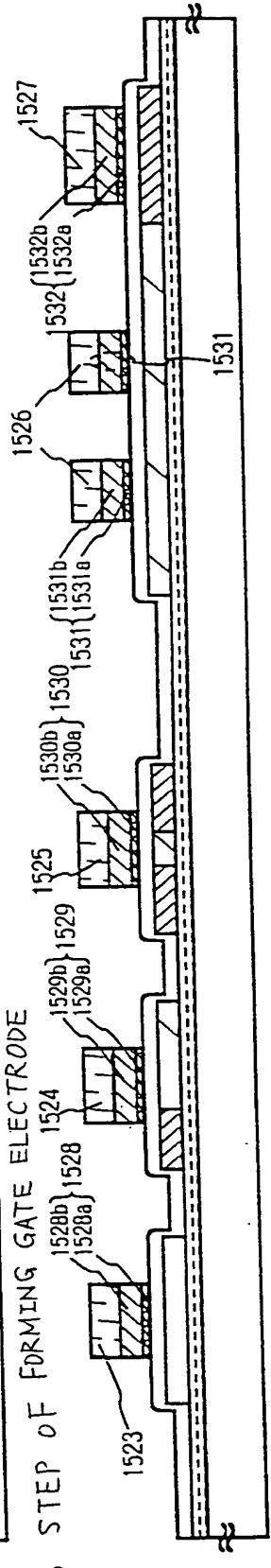


Fig. 16D

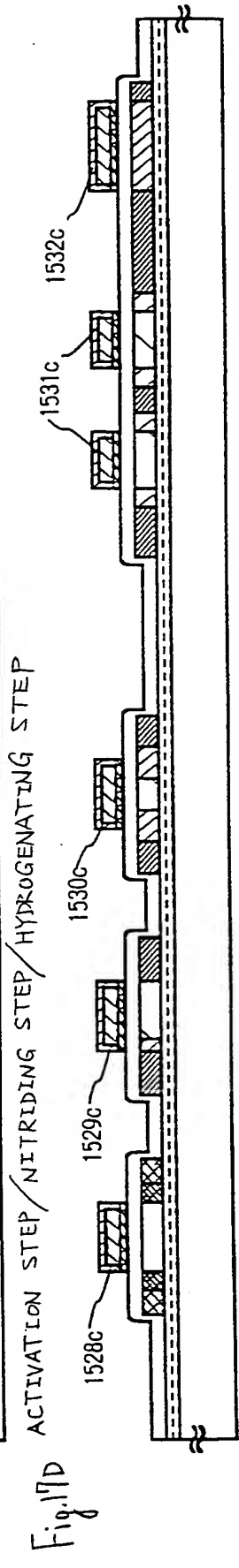
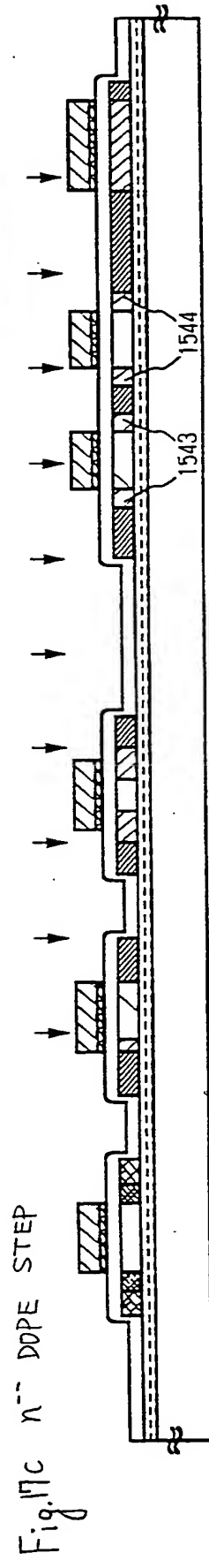
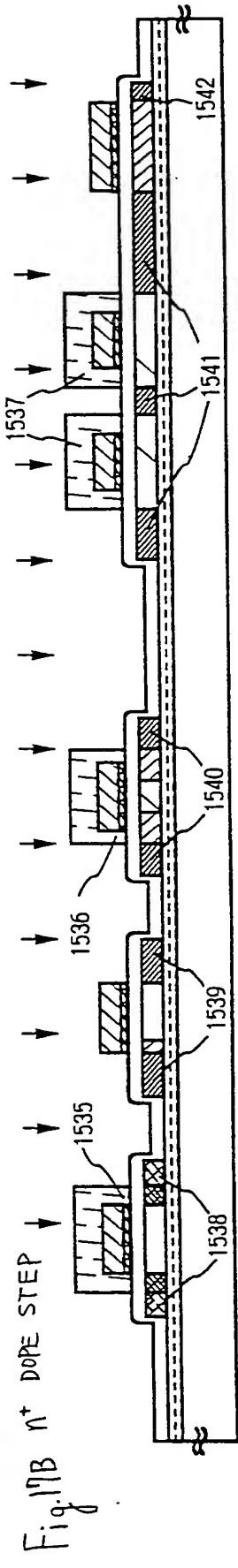
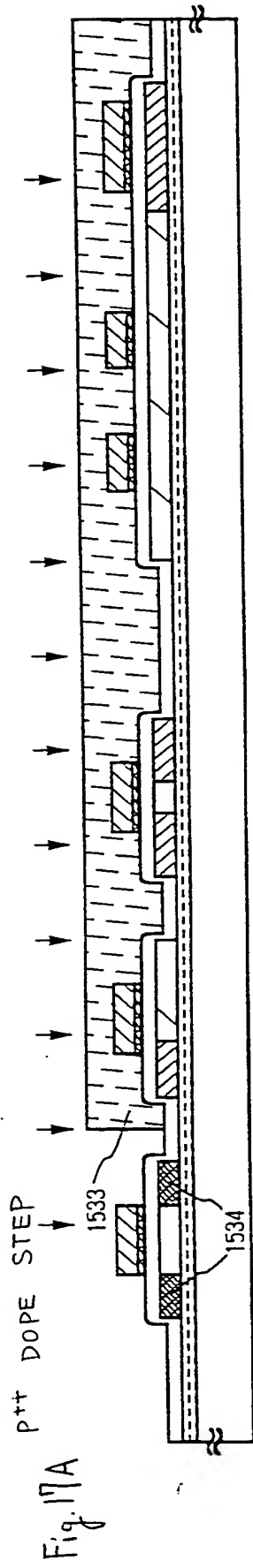


Fig. 18A STEP OF FORMING SECOND CONDUCTIVE FILM

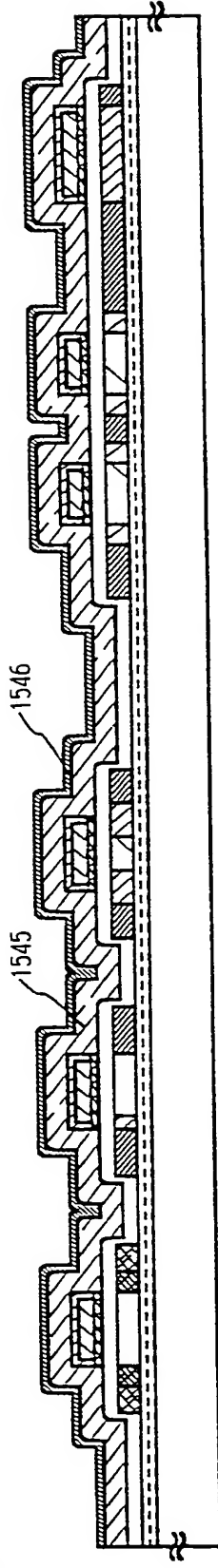


Fig. 18B FORMATION OF GATE WIRING

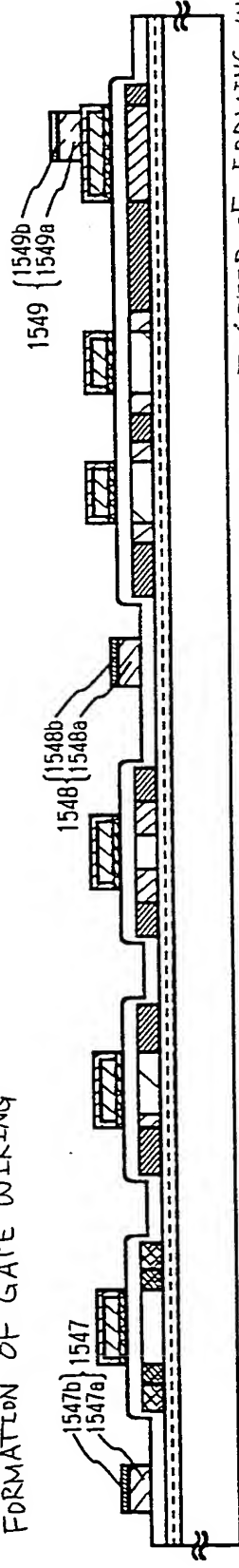


Fig. 18C STEP OF FORMING INTERLAYER INSULATING FILM / STEP OF FORMING CONTACT HOLE / STEP OF FORMING WIRING

Fig. 18C STEP OF FORMING PASSIVATION FILM

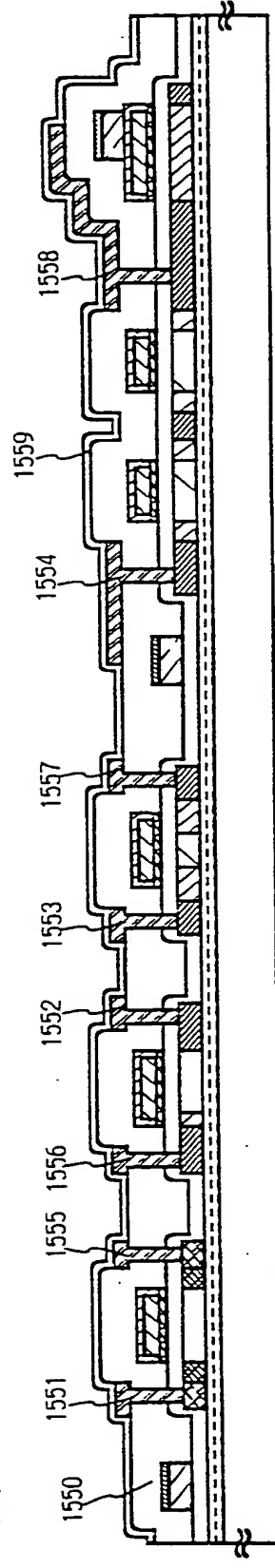
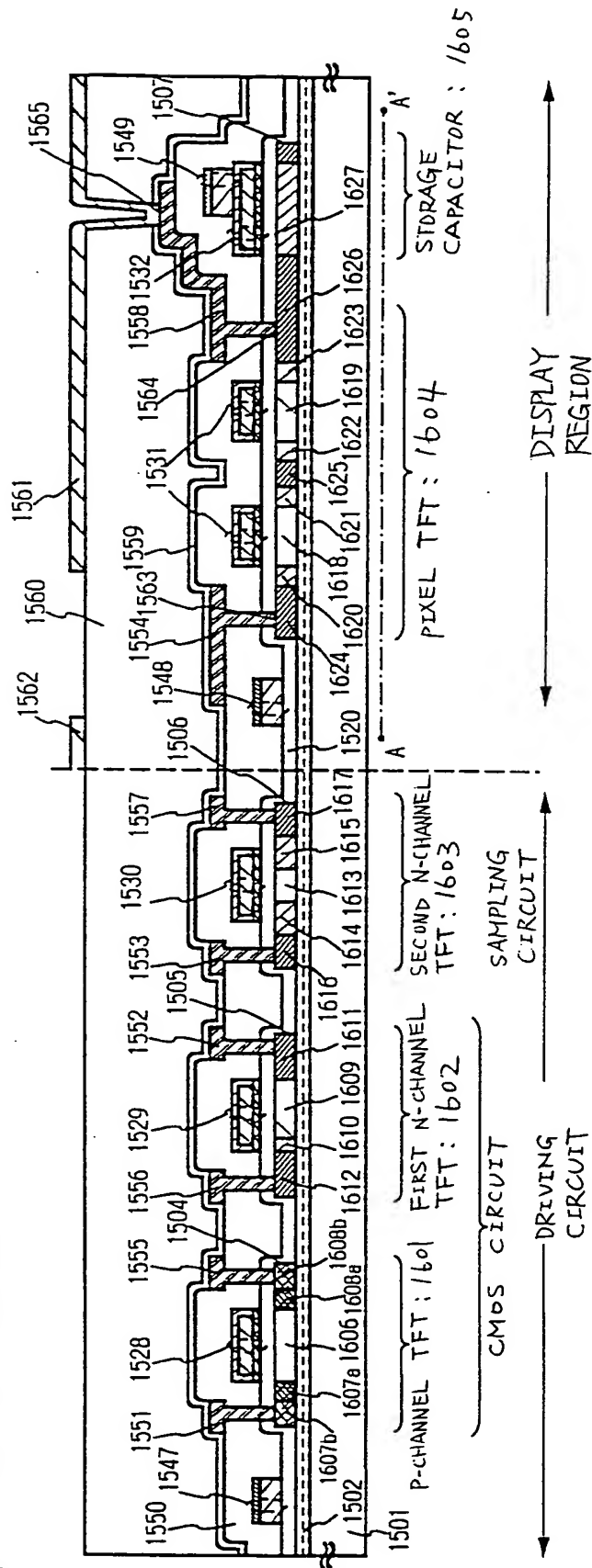


Fig. 19

STEP OF FORMING RESIN FILM	STEP OF FORMING CONTACT HOLE	STEP OF FORMING PIXEL ELECTRODE
	1562	1561
	1560	1565



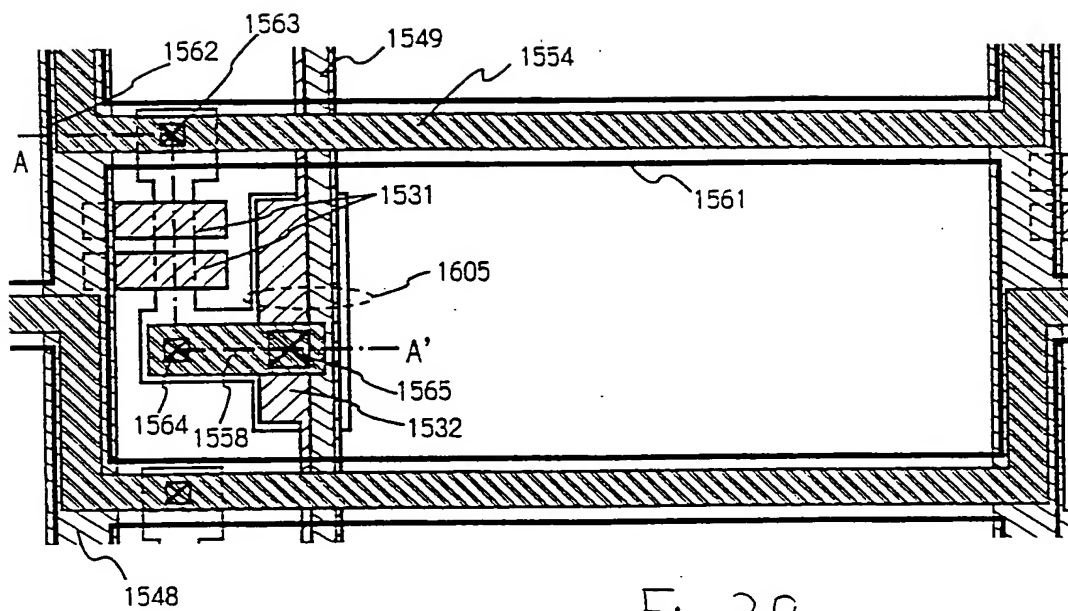


Fig. 20

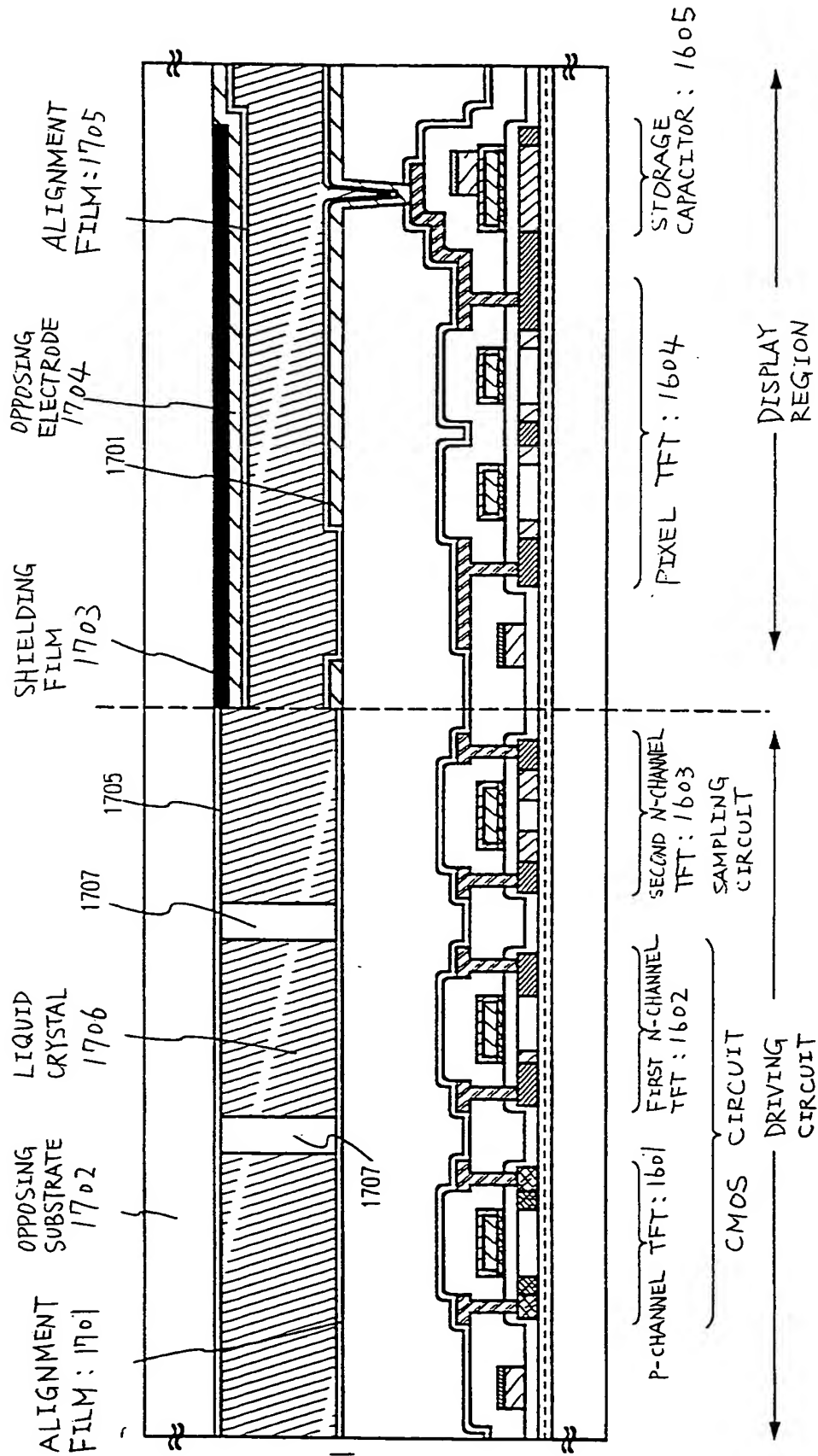


Fig. 21

Fig. 22A STEP OF FORMING AMORPHOUS SEMICONDUCTOR FILM

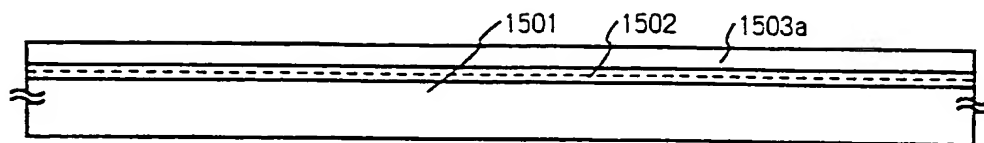


Fig. 22B STEP OF ADDING CATALYST ELEMENT 1801

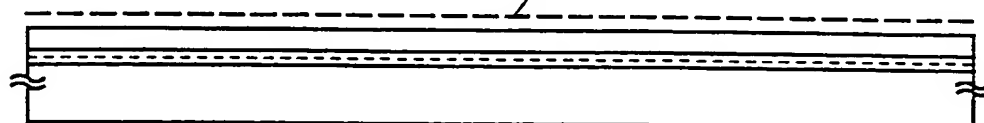


Fig. 22C LASER CRYSTALLIZATION STEP 1802

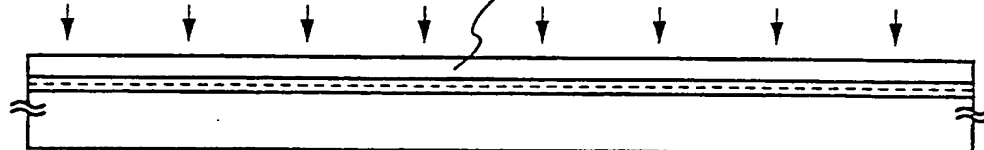


Fig. 23A STEP OF FORMING AMORPHOUS SEMICONDUCTOR FILM

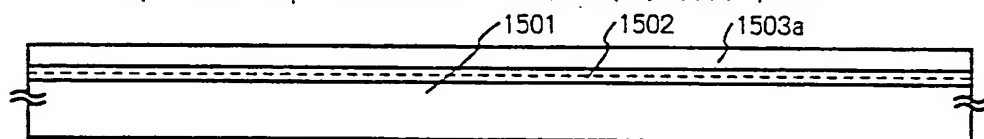


Fig. 23B STEP OF ADDING CATALYST ELEMENT 1901

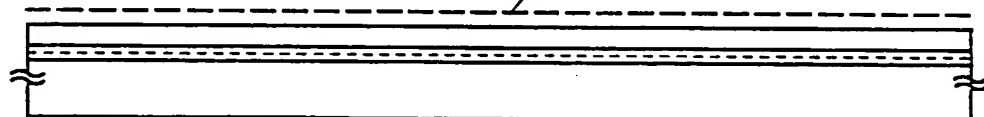


Fig. 23C CRYSTALLIZATION STEP (THERMAL CRYSTALLIZATION) 1902

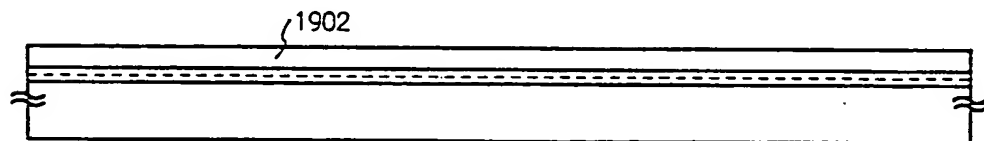
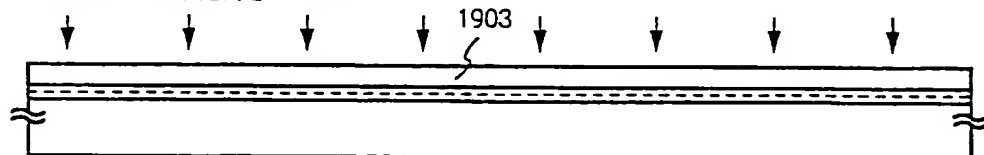


Fig. 23D LASER ANNEAL STEP 1903



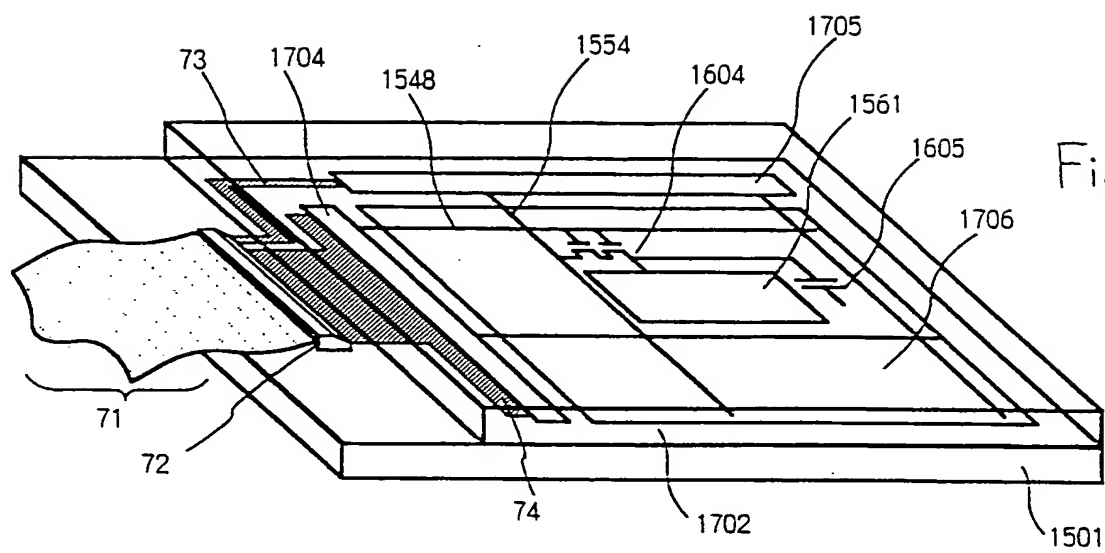


Fig. 24

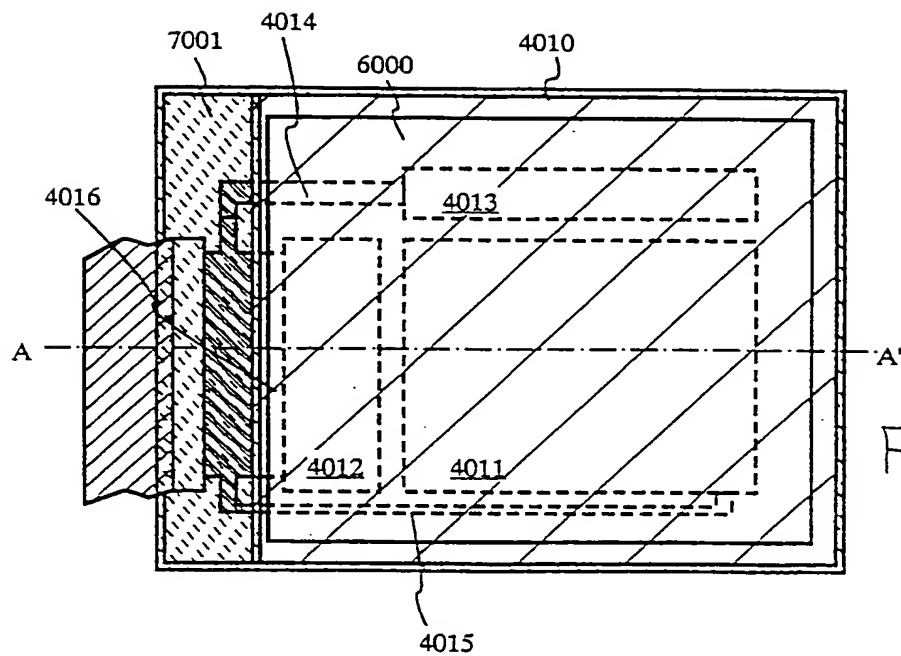


Fig. 25A

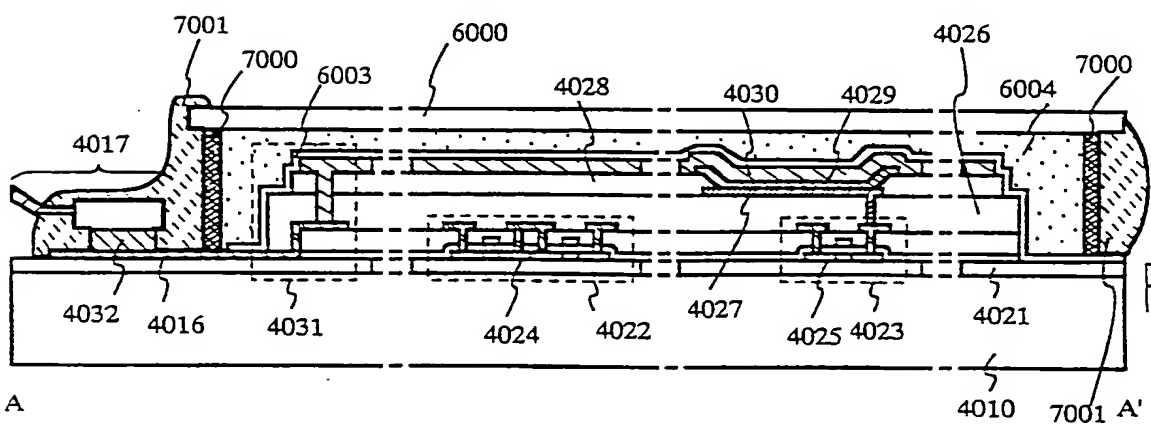


Fig. 25B

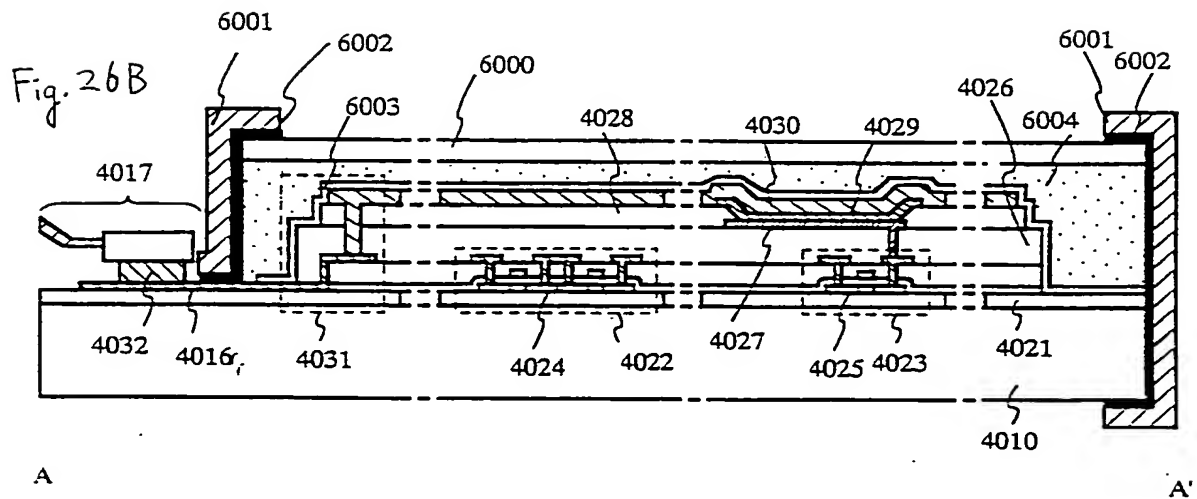
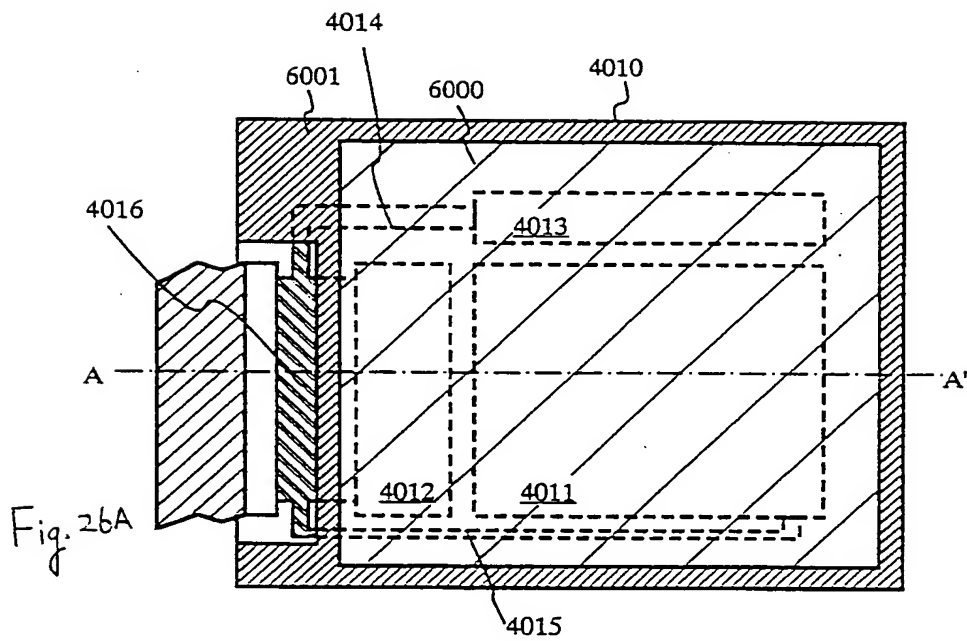


Fig. 28A

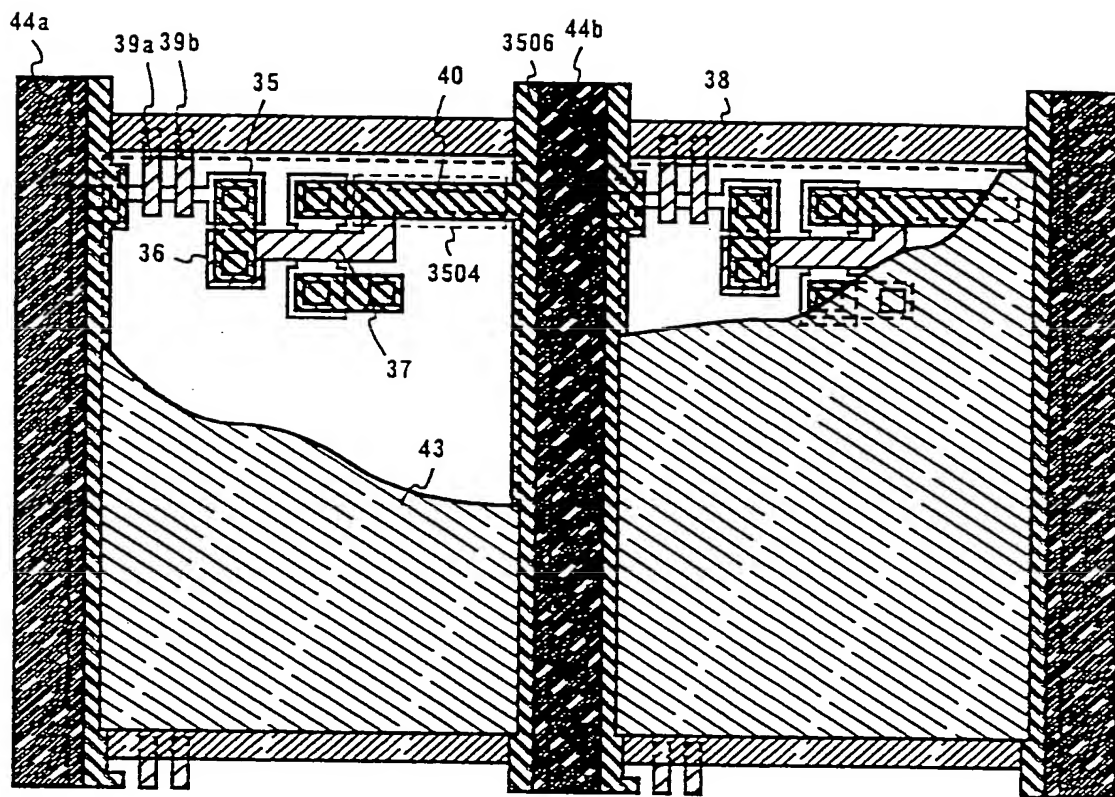
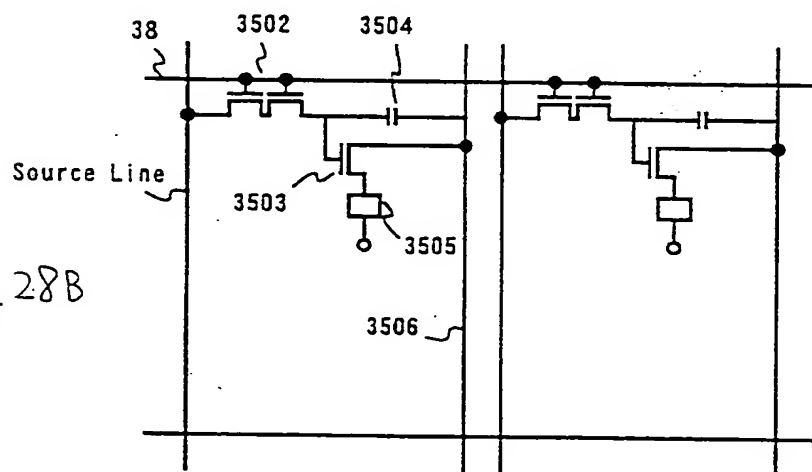


Fig. 28B



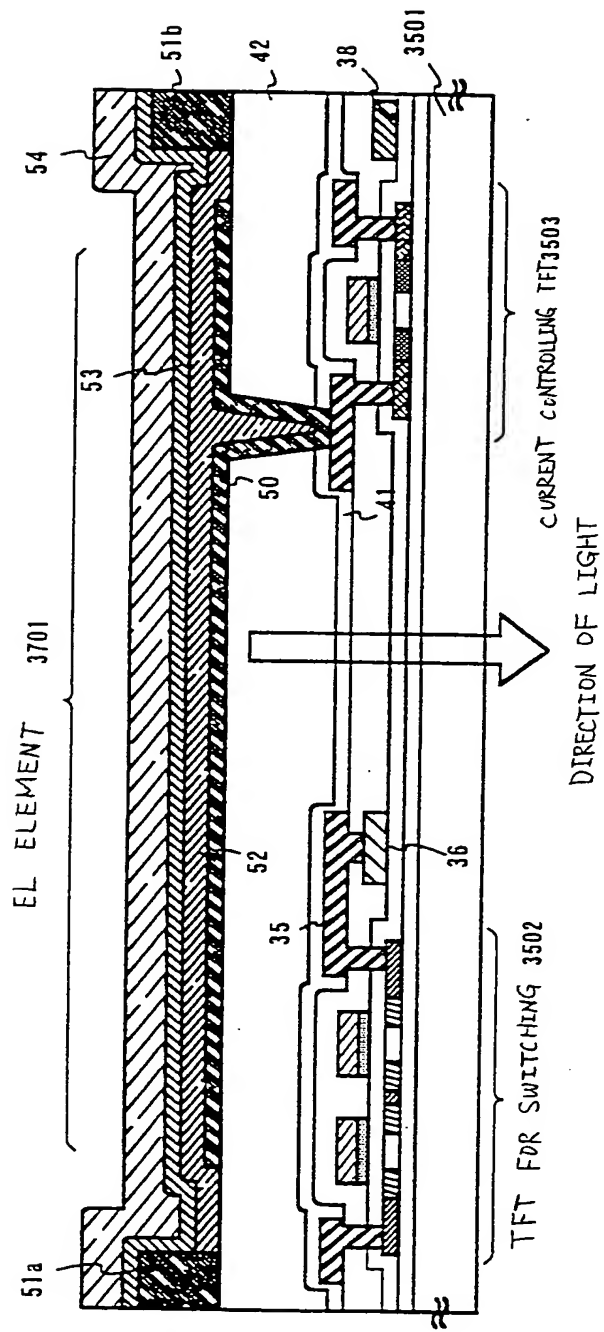


Fig. 29

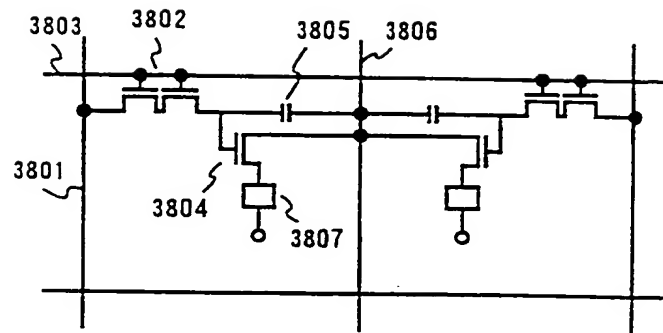


Fig. 30(A)

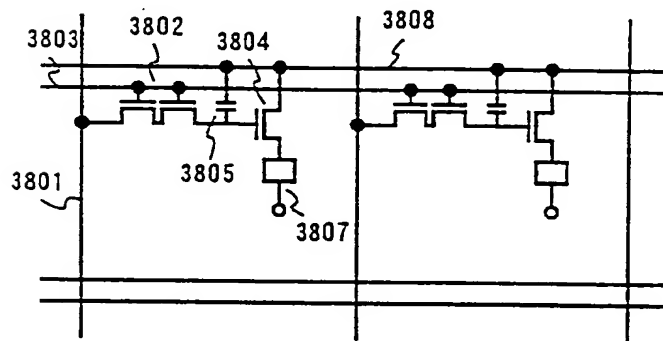


Fig. 30(B)

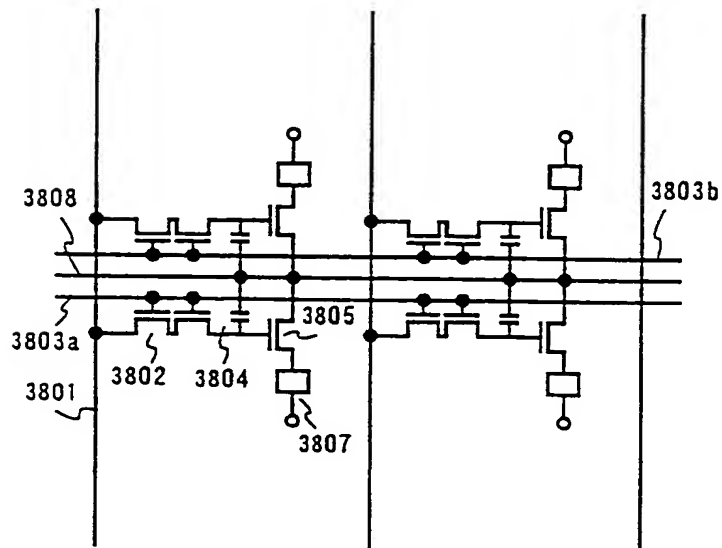
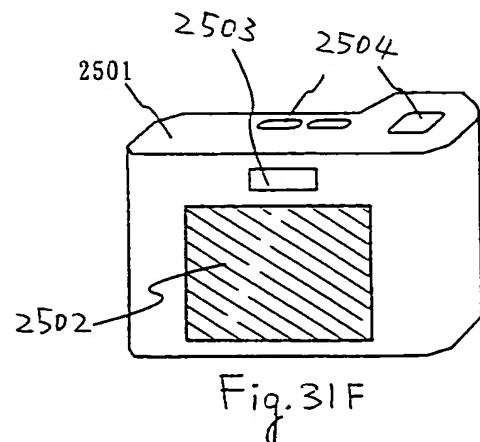
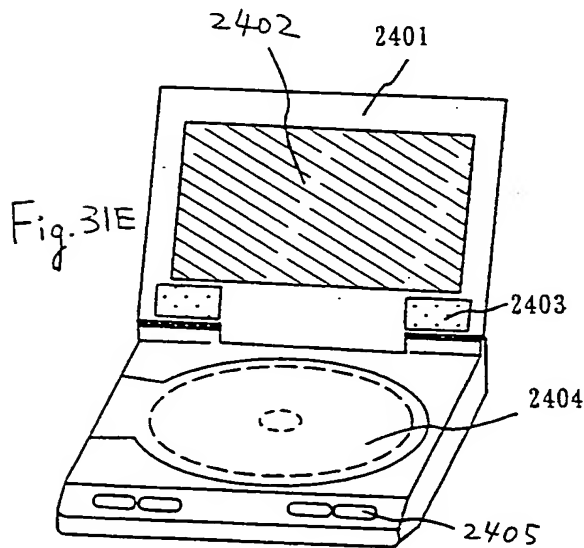
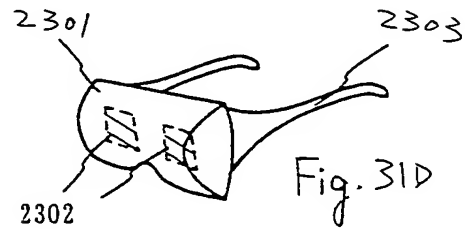
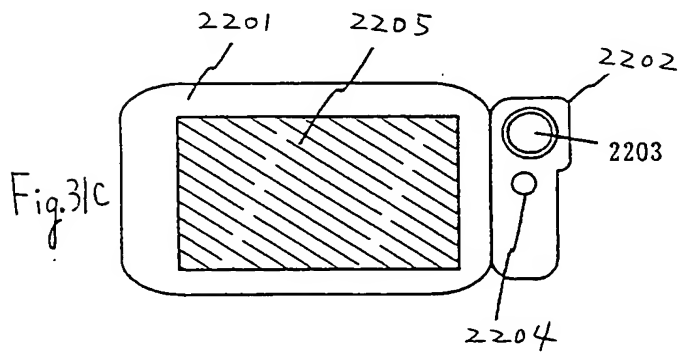
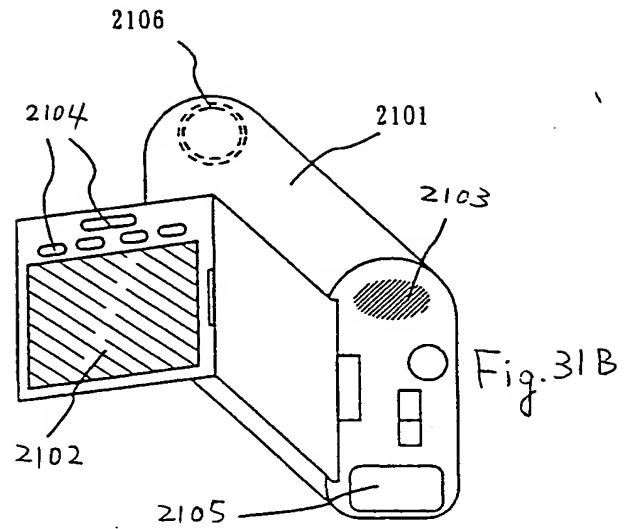
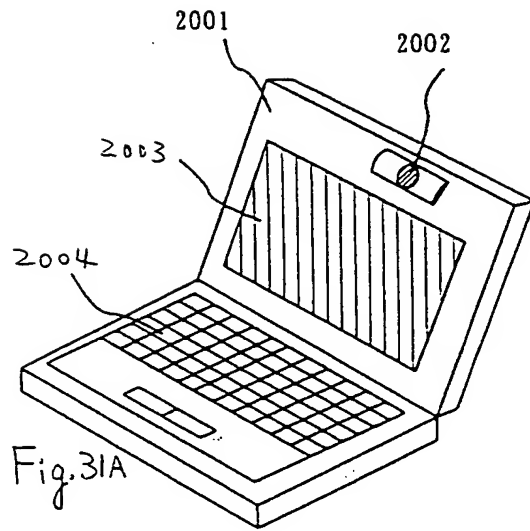


Fig. 30(c)



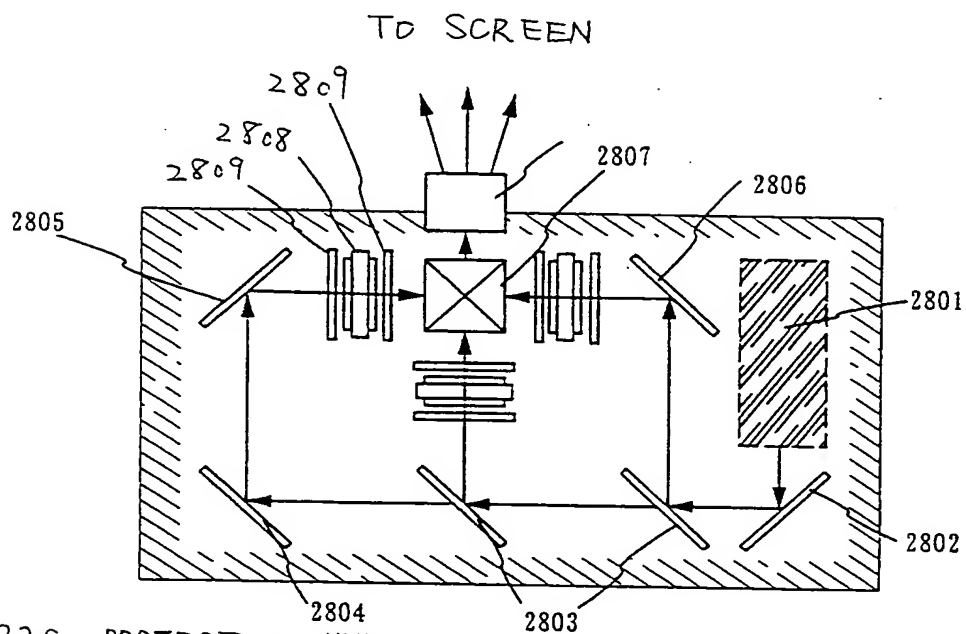
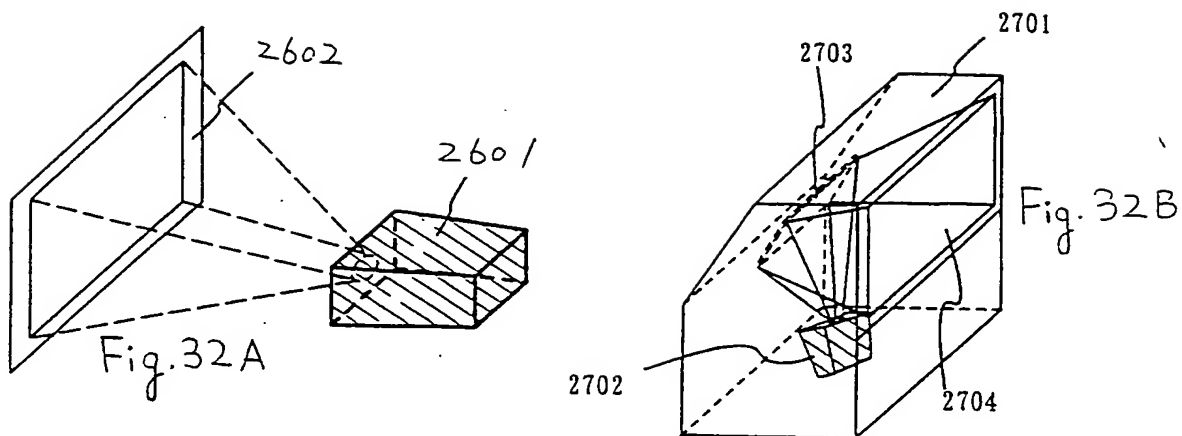


Fig. 32C PROJECTION UNIT
(THREE PLATE SYSTEM)

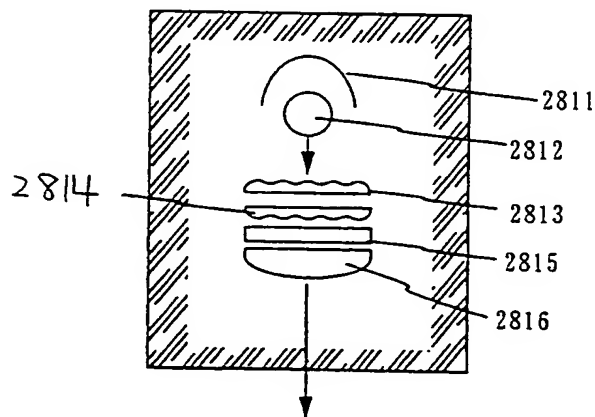


Fig. 32D
LIGHT SOURCE OPTICAL SYSTEM

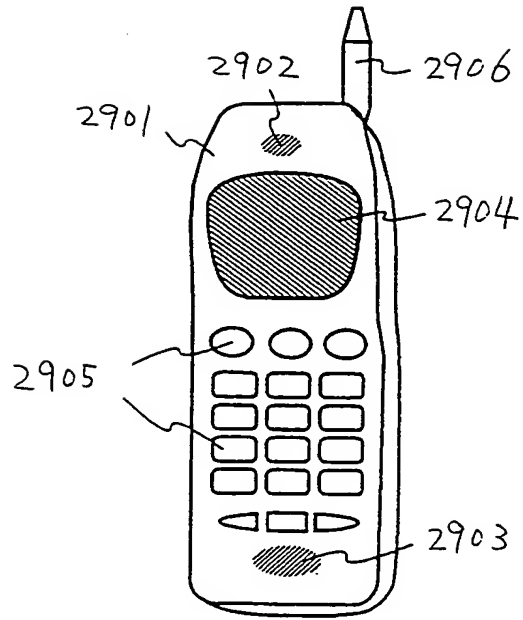


Fig. 33A

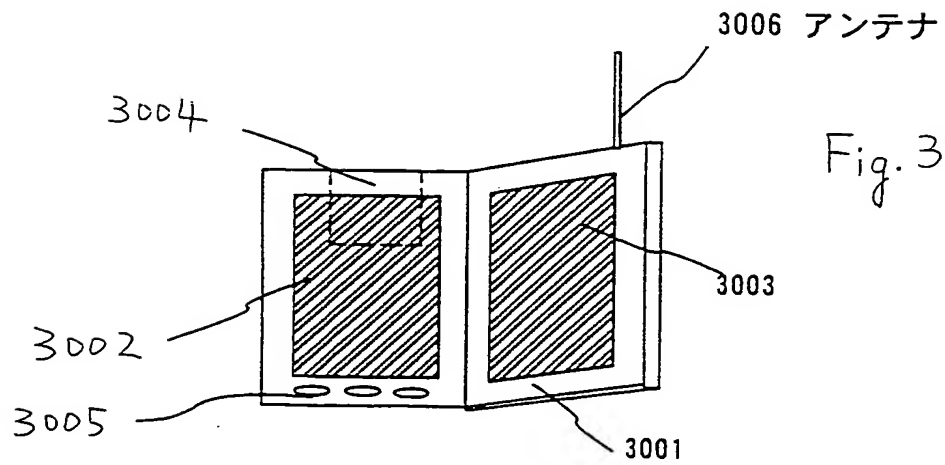


Fig. 33B

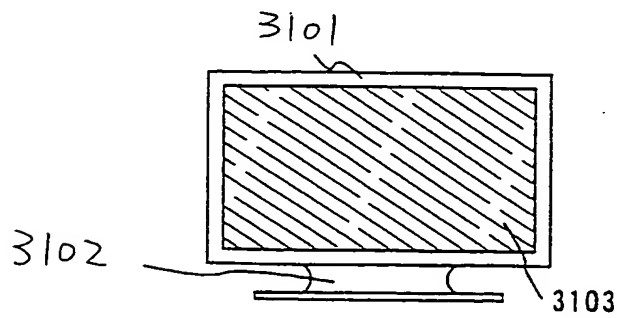


Fig. 33C

ABSORPTION RATIO TO 55 nm - THICK NON-SINGLE CRYSTAL SILICON FILM

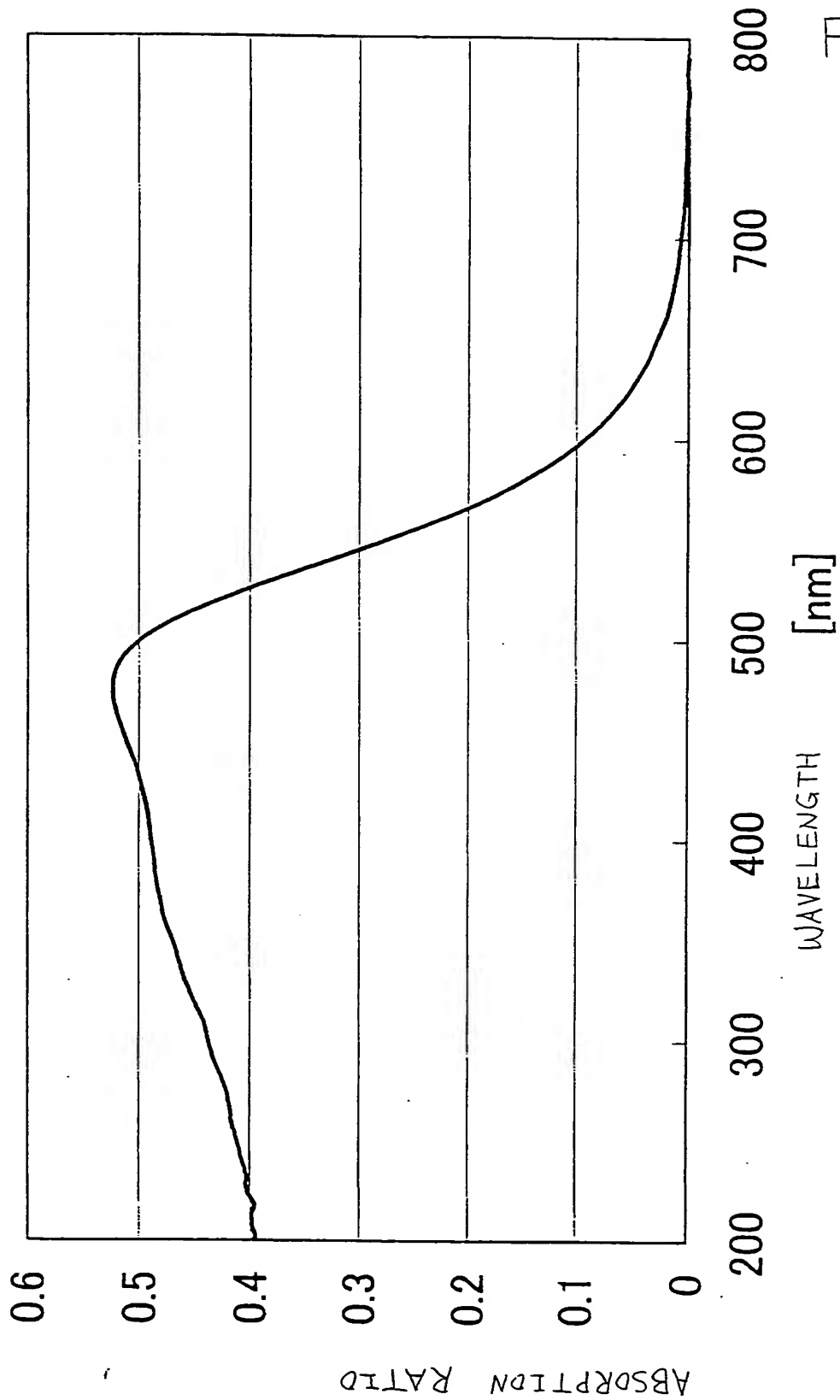


Fig. 34